Claims

1. A deposition apparatus comprising:

a source unit configured to generate a plasma by arc discharge;

a deposition unit in which a deposition target material is arranged so as to be irradiated with the plasma generated in the source unit; and

an induction unit configured to induce the plasma for the source unit to the deposition unit,

wherein the induction unit comprises:

a partition unit airtightly connected to each of the source unit and the deposition unit and configured to pass the plasma inside; and

a plurality of magnet units arranged outside the partition unit and configured to form a magnetic field to induce the plasma in the partition unit,

the plurality of magnet units are connected to adjust a connection angle, and

the partition unit includes a tubular member bendable according to the connection angle of the plurality of magnet units.

2. The apparatus according to claim 1, wherein the plurality of magnet units is deformable, by adjusting the connection angle, to a first state in which the partition unit is bent to induce the plasma from the source unit to the deposition unit and a second state in which the partition unit is stretched straight to

detach the partition unit from the plurality of magnet units.

3. The apparatus according to claim 2, further comprising a hinge mechanism including hinge blocks and a rotation shaft configured to connect the plurality of magnet units, a first stopper configured to hold the plurality of magnet units in the first state, and a second stopper configured to hold the plurality of magnet units in the second state.

4. The apparatus according to any one of claims 1 to 3, wherein each of the magnet units comprises a metal tube, and an electromagnetic coil wound around the metal tube, and

the induction unit to which the plurality of magnet units are connected has a flange unit at one end connected to the source unit and a flange unit at the other end connected to the deposition unit.

5. The apparatus according to any one of claims 1 to 4, wherein the partition unit further comprises a baffle provided in the tubular member and configured to remove particles in the plasma.